ABSTRACT

INTEGRATED CIRCUIT SYSTEM EMPLOYING SACRIFICIAL SPACERS

An integrated circuit system that includes: providing a substrate including a first device and a second device; configuring the first device and the second device to include a first spacer, a first liner made from a first dielectric layer, and a second spacer made from a sacrificial spacer material; forming a second dielectric layer over the integrated circuit system; forming a first device source/drain and a second device source/drain adjacent the second spacer and through the second dielectric layer; removing the second spacer without damaging the substrate; forming a third dielectric layer over the integrated circuit system before annealing; and forming a fourth dielectric layer over the integrated circuit system that promotes stress within the channel of the first device, the second device, or a combination thereof.

FIG. 5